	Hits	Search Text	DBs
34	29	((resist or photoresist)) and (resin$4 same (polyvinyl near16 (aryl or benzyl or phenyl) near15 (acetal or ether or ester))) and (surfactant same (non$4ionic or cationic or anionic or amphoteric))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
35	31	((resist or photoresist)) and (resin$4 same (polyvinyl near16 (aryl or benzyl or phenyl) near15 (acetal or ether or ester))) and (surfactant same (non$4ionic or cationic or anionic or amphoteric or polyoxyalkylene or polyoxyethylene))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
36	24	((resist or photoresist) same pattern) and (resin$4 same (polyvinyl near16 (aryl or benzyl or phenyl) near15 (acetal or ether or ester))) and (surfactant same (non$4ionic or cationic or anionic or amphoteric or polyoxyalkylene or polyoxyethylene))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB